

WASHING METHOD FOR SILICON WAFER

Patent number: JP54034751
Publication date: 1979-03-14
Inventor: SHIBUYA HIDEO; TAKANO JIYUNICHI
Applicant: HITACHI LTD
Classification:
- International: H01L21/30
- european:
Application number: JP19770100473 19770824
Priority number(s): JP19770100473 19770824

Report a data error here

Abstract of JP54034751

PURPOSE: To oxidize and remove foreign matter on a Si substrate surface while supplying O₃ into a washing solution.

Data supplied from the esp@cenet database - Worldwide